



Day : Saturday
Date: 2/5/2005
Time: 17:51:54

Inventor Name Search Result

Your Search was:

Last Name = SUGETA

First Name = YOSHIKI

Application#	Patent#	Status	Date Filed	Title	Inventor Name 21
10948311	Not Issued	030	09/24/2004	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	SUGETA, YOSHIKI
10691537	Not Issued	030	10/24/2003	METHOD OF FORMING FINE PATTERNS	SUGETA, YOSHIKI
10681145	Not Issued	030	10/09/2003	METHOD OF FORMING FINE PATTERNS	SUGETA, YOSHIKI
10644738	Not Issued	030	08/21/2003	METHOD OF FORMING FINE PATTERNS	SUGETA, YOSHIKI
10644737	Not Issued	030	08/21/2003	OVER-COATING AGENT FOR FORMING FINE PATTERNS AND A METHOD OF FORMING FINE PATTERNS USING SUCH AGENT	SUGETA, YOSHIKI
10602883	Not Issued	030	06/25/2003	METHOD OF FORMING FINE PATTERNS	SUGETA, YOSHIKI
10601705	Not Issued	041	06/24/2003	OVER-COATING AGENT FOR FORMING FINE PATTERNS AND A METHOD OF FORMING FINE PATTERNS USING SUCH AGENT	SUGETA, YOSHIKI
10471772	Not Issued	030	03/02/2004	AGENT FOR FORMING COATING FOR NARROWING PATTERNS AND METHOD FOR FORMING FINE PATTERN USING THE SAME	SUGETA, YOSHIKI
10471771	Not Issued	030	03/02/2004	METHOD FOR FORMING FINE PATTERNS	SUGETA, YOSHIKI
10315190	Not Issued	071	12/10/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	SUGETA, YOSHIKI
10315065	6811817	150	12/10/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	SUGETA, YOSHIKI

<u>10173880</u>	Not Issued	041	06/19/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	SUGETA, YOSHIKI
<u>09707890</u>	<u>6399275</u>	150	11/08/2000	NEGATIVE-WORKING PHOTOLITHOGRAPHIC PATTERNING MATERIAL AND METHOD FOR THE PREPARATION OF ION- IMPLANTED AND METAL- PLATED SUBSTRATES BY USING THE SAME	SUGETA, YOSHIKI
<u>09236612</u>	<u>6063953</u>	150	01/26/1999	CHEMICAL-SENSITIZATION PHOTORESIST COMPOSITION	SUGETA , YOSHIKI
<u>09236567</u>	<u>6022666</u>	150	01/26/1999	CHEMICAL-SENSITIZATION PHOTORESIST COMPOSITION	SUGETA , YOSHIKI
<u>09179818</u>	<u>5973187</u>	150	10/28/1998	POSITIVE-WORKING CHEMICAL-SENSITIZATION PHOTORESIST COMPOSITION	SUGETA , YOSHIKI
<u>09179817</u>	<u>5990338</u>	150	10/28/1998	NEGATIVE-WORKING CHEMICAL -SENSITIZATION PHOTORESIST COMPOSITION	SUGETA , YOSHIKI
<u>09161778</u>	<u>6042988</u>	150	09/29/1998	CHEMICAL-AMPLIFICATION- TYPE NEGATIVE RESIST COMPOSITION	SUGETA , YOSHIKI
<u>08987023</u>	<u>5928837</u>	150	12/09/1997	NEGATIVE-WORKING CHEMICAL-SENSITIZATION PHOTORESIST COMPOSITION COMPRISING OXIME SULFONATE COMPOUNDS	SUGETA , YOSHIKI
<u>08956792</u>	<u>5955241</u>	150	10/23/1997	CHEMICAL-AMPLIFICATION- TYPE NEGATIVE RESIST COMPOSITION AND METHOD FOR FORMING NEGATIVE RESIST PATTERN	SUGETA , YOSHIKI
<u>08762920</u>	<u>5902713</u>	150	12/10/1996	CHEMICAL-SENSITIZATION PHOTORESIST COMPOSITION	SUGETA , YOSHIKI

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PALM INTRANET

Day : Saturday
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Inventor Name Search Result

Your Search was:

Last Name = KANEKO

First Name = FUMITAKE

Application#	Patent#	Status	Date Filed	Title	Inventor Name 28
<u>10948311</u>	Not Issued	030	09/24/2004	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	KANEKO, FUMITAKE
<u>10901207</u>	Not Issued	030	07/29/2004	MULTILAYERED BODY FOR PHOTOLITHOGRAPHIC PATTERNING	KANEKO, FUMITAKE
<u>10691537</u>	Not Issued	030	10/24/2003	METHOD OF FORMING FINE PATTERNS	KANEKO, FUMITAKE
<u>10681145</u>	Not Issued	030	10/09/2003	METHOD OF FORMING FINE PATTERNS	KANEKO, FUMITAKE
<u>10644737</u>	Not Issued	030	08/21/2003	OVER-COATING AGENT FOR FORMING FINE PATTERNS AND A METHOD OF FORMING FINE PATTERNS USING SUCH AGENT	KANEKO, FUMITAKE
<u>10602883</u>	Not Issued	030	06/25/2003	METHOD OF FORMING FINE PATTERNS	KANEKO, FUMITAKE
<u>10601705</u>	Not Issued	041	06/24/2003	OVER-COATING AGENT FOR FORMING FINE PATTERNS AND A METHOD OF FORMING FINE PATTERNS USING SUCH AGENT	KANEKO, FUMITAKE
<u>10471772</u>	Not Issued	030	03/02/2004	AGENT FOR FORMING COATING FOR NARROWING PATTERNS AND METHOD FOR FORMING FINE PATTERN USING THE SAME	KANEKO, FUMITAKE
<u>10471771</u>	Not Issued	030	03/02/2004	METHOD FOR FORMING FINE PATTERNS	KANEKO, FUMITAKE
<u>10315190</u>	Not Issued	071	12/10/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	KANEKO, FUMITAKE
<u>10315065</u>	<u>6811817</u>	150	12/10/2002	METHOD FOR REDUCING PATTERN DIMENSION IN	KANEKO, FUMITAKE

				PHOTORESIST LAYER	
<u>10173880</u>	Not Issued	041	06/19/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	KANEKO, FUMITAKE
<u>10160160</u>	Not Issued	161	06/04/2002	MULTILAYERED BODY FOR PHOTOLITHOGRAPHIC PATTERNING	KANEKO, FUMITAKE
<u>10053622</u>	Not Issued	095	01/24/2002	NEGATIVE-WORKING PHOTORESIST COMPOSITION	KANEKO, FUMITAKE
<u>09641686</u>	<u>6455228</u>	150	08/18/2000	MULTILAYERED BODY FOR PHOTOLITHOGRAPHIC PATTERNING	KANEKO, FUMITAKE
<u>09638872</u>	<u>6406829</u>	150	08/15/2000	NEGATIVE-WORKING PHOTORESIST COMPOSITION	KANEKO, FUMITAKE
<u>09425369</u>	<u>6544712</u>	150	10/22/1999	NEGATIVE WORKING RESIST COMPOSITION	KANEKO , FUMITAKE
<u>09317208</u>	<u>6245930</u>	150	05/24/1999	CHEMICAL-SENSITIZATION RESIST COMPOSITION	KANEKO , FUMITAKE
<u>09273262</u>	<u>6083665</u>	150	03/22/1999	PHOTORESIST LAMINATE AND METHOD FOR PATTERNING USING THE SAME	KANEKO , FUMITAKE
<u>09271899</u>	<u>6087068</u>	150	03/18/1999	UNDERCOATING COMPOSITION FOR PHOTOLITHOGRAPHIC RESIST	KANEKO , FUMITAKE
<u>09239798</u>	<u>6171749</u>	150	01/29/1999	NEGATIVE-WORKING CHEMICAL-AMPLIFICATION PHOTORESIST COMPOSITION	KANEKO , FUMITAKE
<u>09161778</u>	<u>6042988</u>	150	09/29/1998	CHEMICAL-AMPLIFICATION- TYPE NEGATIVE RESIST COMPOSITION	KANEKO , FUMITAKE
<u>08997050</u>	Not Issued	161	12/23/1997	CHEMICAL-AMPLIFICATION- TYPE NEGATIVE RESIST COMPOSITION	KANEKO , FUMITAKE
<u>08924260</u>	<u>5925495</u>	150	09/05/1997	PHOTORESIST LAMINATE AND METHOD FOR PATTERNING USING THE SAME	KANEKO , FUMITAKE
<u>08898105</u>	<u>5976760</u>	150	07/22/1997	CHEMICAL-SENSITIZATION RESIST COMPOSITION	KANEKO , FUMITAKE
<u>08845358</u>	<u>5939510</u>	150	04/24/1997	UNDERCOATING COMPOSITION FOR PHOTOLITHOGRAPHIC RESIST	KANEKO , FUMITAKE

<u>08630621</u>	<u>5700625</u>	150	04/10/1996	NEGATIVE-WORKING PHOTORESIST COMPOSITON	KANEKO , FUMITAKE
<u>08626147</u>	<u>5789136</u>	150	04/05/1996	NEGATIVE-WORKING PHOTORESIST COMPOSITION	KANEKO , FUMITAKE

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Inventor Name Search Result

Your Search was:

Last Name = TACHIKAWA

First Name = TOSHIKAZU

Application#	Patent#	Status	Date Filed	Title	Inventor Name 25
<u>10948311</u>	Not Issued	030	09/24/2004	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	TACHIKAWA, TOSHIKAZU
<u>10901207</u>	Not Issued	030	07/29/2004	MULTILAYERED BODY FOR PHOTOLITHOGRAPHIC PATTERNING	TACHIKAWA, TOSHIKAZU
<u>10845620</u>	Not Issued	020	05/13/2004	RESIST COMPOSITION	TACHIKAWA, TOSHIKAZU
<u>10808425</u>	Not Issued	030	03/25/2004	NEGATIVE RESIST MATERIAL AND METHOD FOR FORMING RESIST PATTERN	TACHIKAWA, TOSHIKAZU
<u>10691537</u>	Not Issued	030	10/24/2003	METHOD OF FORMING FINE PATTERNS	TACHIKAWA, TOSHIKAZU
<u>10681145</u>	Not Issued	030	10/09/2003	METHOD OF FORMING FINE PATTERNS	TACHIKAWA, TOSHIKAZU
<u>10644738</u>	Not Issued	030	08/21/2003	METHOD OF FORMING FINE PATTERNS	TACHIKAWA, TOSHIKAZU
<u>10644737</u>	Not Issued	030	08/21/2003	OVER-COATING AGENT FOR FORMING FINE PATTERNS AND A METHOD OF FORMING FINE PATTERNS USING SUCH AGENT	TACHIKAWA, TOSHIKAZU
<u>10603511</u>	Not Issued	071	06/25/2003	NEGATIVE RESIST COMPOSITION	TACHIKAWA, TOSHIKAZU
<u>10602883</u>	Not Issued	030	06/25/2003	METHOD OF FORMING FINE PATTERNS	TACHIKAWA, TOSHIKAZU
<u>10601705</u>	Not Issued	041	06/24/2003	OVER-COATING AGENT FOR FORMING FINE PATTERNS AND A METHOD OF FORMING FINE PATTERNS USING SUCH AGENT	TACHIKAWA, TOSHIKAZU
<u>10471772</u>	Not	030	03/02/2004	AGENT FOR FORMING	TACHIKAWA,

	Issued			COATING FOR NARROWING PATTERNS AND METHOD FOR FORMING FINE PATTERN USING THE SAME	TOSHIKAZU
<u>10471771</u>	Not Issued	030	03/02/2004	METHOD FOR FORMING FINE PATTERNS	TACHIKAWA, TOSHIKAZU
<u>10315190</u>	Not Issued	071	12/10/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	TACHIKAWA, TOSHIKAZU
<u>10315065</u>	<u>6811817</u>	150	12/10/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	TACHIKAWA, TOSHIKAZU
<u>10173880</u>	Not Issued	041	06/19/2002	METHOD FOR REDUCING PATTERN DIMENSION IN PHOTORESIST LAYER	TACHIKAWA, TOSHIKAZU
<u>10160160</u>	Not Issued	161	06/04/2002	MULTILAYERED BODY FOR PHOTOLITHOGRAPHIC PATTERNING	TACHIKAWA, TOSHIKAZU
<u>10053622</u>	Not Issued	095	01/24/2002	NEGATIVE-WORKING PHOTORESIST COMPOSITION	TACHIKAWA, TOSHIKAZU
<u>09641686</u>	<u>6455228</u>	150	08/18/2000	MULTILAYERED BODY FOR PHOTOLITHOGRAPHIC PATTERNING	TACHIKAWA, TOSHIKAZU
<u>09638872</u>	<u>6406829</u>	150	08/15/2000	NEGATIVE-WORKING PHOTORESIST COMPOSITION	TACHIKAWA, TOSHIKAZU
<u>09474263</u>	<u>6276861</u>	150	12/29/1999	WRITING INSTRUMENT	TACHIKAWA, TOSHIKAZU
<u>09425369</u>	<u>6544712</u>	150	10/22/1999	NEGATIVE WORKING RESIST COMPOSITION	TACHIKAWA, TOSHIKAZU
<u>09239798</u>	<u>6171749</u>	150	01/29/1999	NEGATIVE-WORKING CHEMICAL-AMPLIFICATION PHOTORESIST COMPOSITION	TACHIKAWA, TOSHIKAZU
<u>08987023</u>	<u>5928837</u>	150	12/09/1997	NEGATIVE-WORKING CHEMICAL-SENSITIZATION PHOTORESIST COMPOSITION COMPRISING OXIME SULFONATE COMPOUNDS	TACHIKAWA, TOSHIKAZU
<u>07850788</u>	Not Issued	161	03/13/1992	BINDER RINGS	TACHIKAWA, TOSHIKAZU

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